

Refine Search

Search Results -

Terms	Documents
(plasma same (hydrogen and nitrogen)) and (plasma with etch\$5) and ((resist or mask or photoresist) with selectiv\$4)	762

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 DATE: Monday, April 11, 2005 [Printable Copy](#) [Create Case](#)

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L1 (plasma same (hydrogen and nitrogen)) and (plasma with etch\$5) and
 ((resist or mask or photoresist) with selectiv\$4)

762 L1

END OF SEARCH HISTORY